

Measurement of Residual Stresses in Single Crystal Cubic Materials Using X-Ray Diffraction Technique

应用X射线衍射技术测量立方结构单晶材料的残余应力

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Material Microstructures 材料微观结构

- Polycrystalline with coarse grain structure oriented (with preferred orientation)

多晶粗粒结构沿一定方向取向

- Directional solidified grain structure

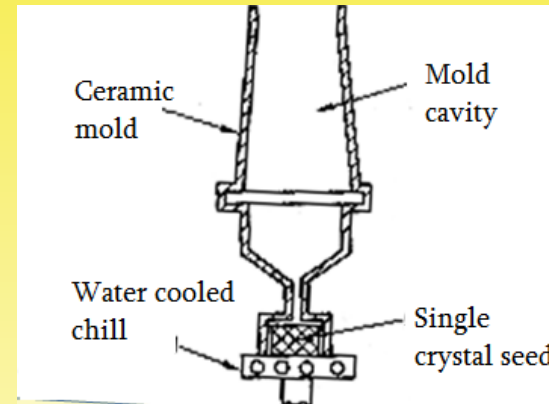
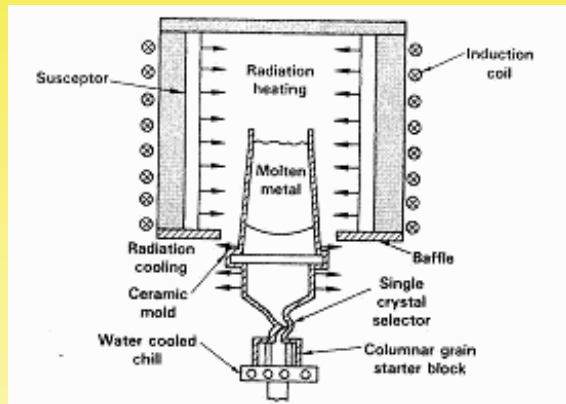
沿一定方向强化的晶粒结构

- Single Crystal structure

单晶结构

Fabrication of Material Components

材料部件的制造 Single Crystal Materials 单晶材料

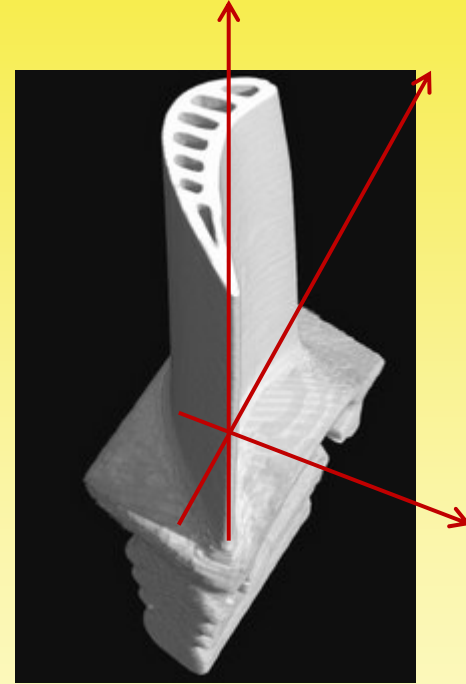


**Directional solidification Process to cast single Crystals
and equiaxed grains**

使用定向强化工艺从冷却铜版生产单晶(等轴晶粒)

Fabrication of Material Components

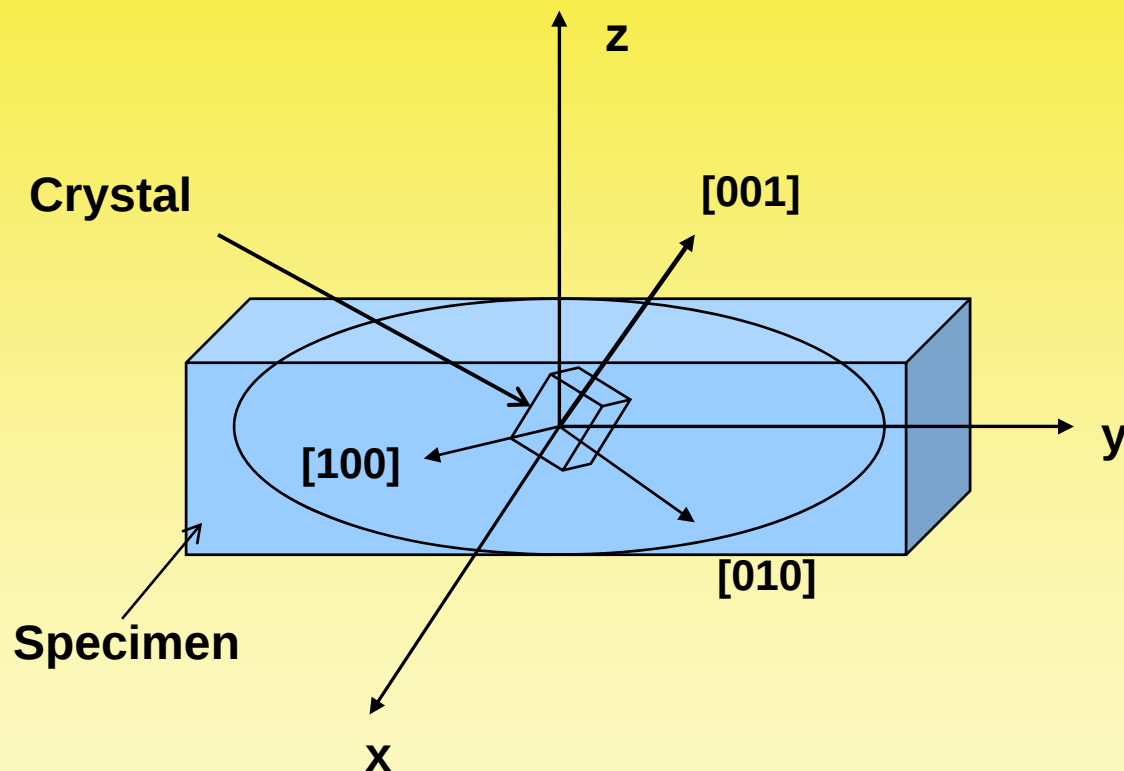
材料部件的制造 Single Crystal Materials 单晶材料



Example of Turbine Blades

Stress Measurement Techniques 应力测量技术

Crystal Orientation (Reference definition) 晶体方向（坐标系定义）

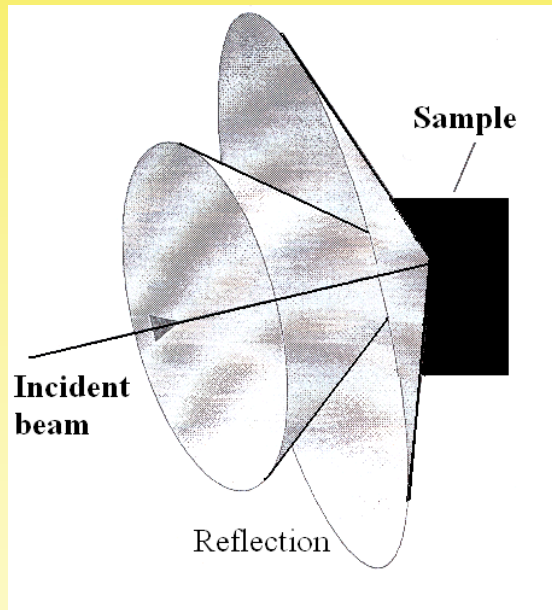


Transition from Crystal to specimen reference

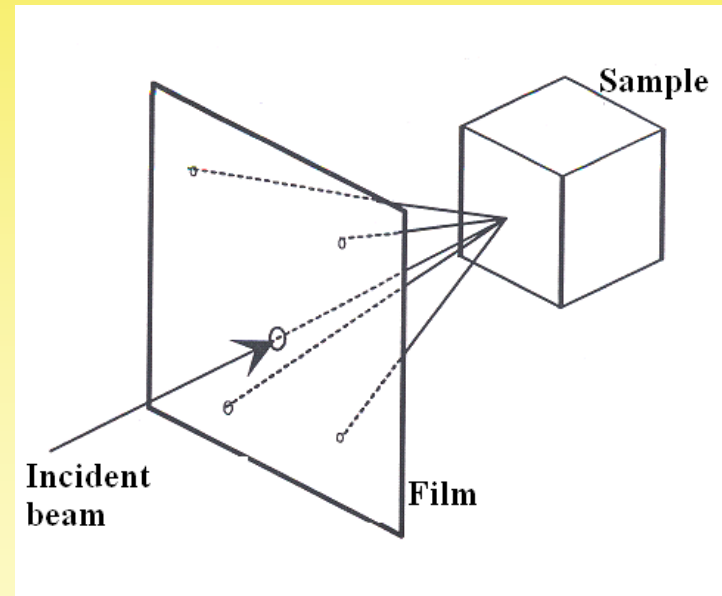
试样坐标系对晶体参照系的变换

Diffraction Techniques 衍射技术

- Polycrystalline Material and Single Crystal Materials
多晶材料和单晶材料



Debye Rings
德拜环



Discrete Poles (LAUE)
劳厄法

Mechanical Behaviour of Materials 材料的机械特性

Single Crystal materials 单晶材料

● Hooke's Law

● Anisotropic materials

各向异性材料

- 81 different components which reduces to 3 for cubic symmetry

对立方体结构, 将81种不同的分量减少到只有三个分量

$$\sigma_{ij} = C_{ijkl} \epsilon_{kl}$$

$$\sigma_{ij} = \begin{pmatrix} \sigma_{11} \\ \sigma_{22} \\ \sigma_{33} \\ \sigma_{23} \\ \sigma_{31} \\ \sigma_{12} \end{pmatrix}, C_{ijkl} = \begin{pmatrix} C_{11} & C_{12} & C_{12} & 0 & 0 & 0 \\ C_{12} & C_{11} & C_{12} & 0 & 0 & 0 \\ C_{12} & C_{12} & C_{11} & 0 & 0 & 0 \\ 0 & 0 & 0 & C_{44} & 0 & 0 \\ 0 & 0 & 0 & 0 & C_{44} & 0 \\ 0 & 0 & 0 & 0 & 0 & C_{44} \end{pmatrix}, \epsilon_{ij} = \begin{pmatrix} \epsilon_{11} \\ \epsilon_{22} \\ \epsilon_{33} \\ \epsilon_{23} \\ \epsilon_{31} \\ \epsilon_{12} \end{pmatrix}$$

Mechanical Behaviour of Materials 材料的机械特性

Single Crystal materials 单晶材料

- Elastic behaviour 弹性特性

- Elastic modulus in one direction 一个方向的弹性模量

$$\frac{1}{E^{[hkl]}} = S_{11} - 2 \left((S_{11} - S_{12}) - \frac{1}{2} S_{44} \right) \Gamma^{[hkl]}$$

$$\Gamma^{[hkl]} = \frac{h^2 k^2 + k^2 l^2 + l^2 h^2}{(h^2 + k^2 + l^2)^2}$$

- $\Gamma^{[100]}=0$, $\Gamma^{[110]}=1/2$, $\Gamma^{[111]}=1/3$

- For isotropic materials $\left((S_{11} - S_{12}) - \frac{1}{2} S_{44} \right) = 0$

Stress Measurement Techniques 应力 测量技术 Single Crystal Material 单晶材料

- Steps for measuring stresses in a single crystal

测量单晶应力的步骤

- Determine the crystal orientation using Pole figure technique or LAUE technique, scan in ϕ and ψ directions using low multiplicity (hkl) plane
利用极图或LAUE技术,确定晶体的方向,用低阶(hkl)平面在 ϕ and ψ 方向扫描
- Select at least 3 poles or more to determine an accurate crystal orientation
选择至少 3 个极点或更多来确定精确的晶体方向
- Index the poles (hkl)
检索极点 (hkl)

Stress Measurement Techniques 应力 测量技术 Single Crystal Material 单晶材料

- Calculate the orientation matrix
计算定向矩阵
- Calculate the poles positions for stress measurements, new (hkl) planes
计算应力测量的极点的位置，新的hkl平面
- Scan in half space around the pole and determine accurately Bragg angle of the peak
对极点进行上半空间空间扫描，决定精确的峰位的Bragg角
- Using the elasticity theory, calculate the stress tensor.
应用弹性理论，计算应力张量

X-Ray Diffraction Equipment

X 射线

衍射仪 Configuration 配置

The equipment should be equipped with the following: 仪器应该有如下配置

- Motorized ψ rotation,
 $0 \leq \psi \leq 60$
自动化 ψ 角旋转范围,
- Motorized ϕ rotation
 $0 \leq \phi \leq 360$
自动化 ϕ 旋转范围,
- Linear detector or 2D detector
线性探测器或二维探测器



Proto LXRD System

X-Ray Diffraction Equipment

X 射线

衍射仪 Configuration 配置

- X-Y stage for easy positioning
自动化的X-Y平台灵活定位
- High power X-ray tube
大功率 X 射线管
- Safety enclosure
带安全锁的机柜
- Control and analytical software
控制和分析软件

Stress Measurement Techniques 应力

测量技术 Alignment verification, ASTM E915 校准验证

Free stress powder: 316L 无应力 316L 粉

X-Ray tube: Mn 靶材

Plane (hkl): 311 晶面

Bragg angle, $2\theta = 152^\circ$ 布拉格角

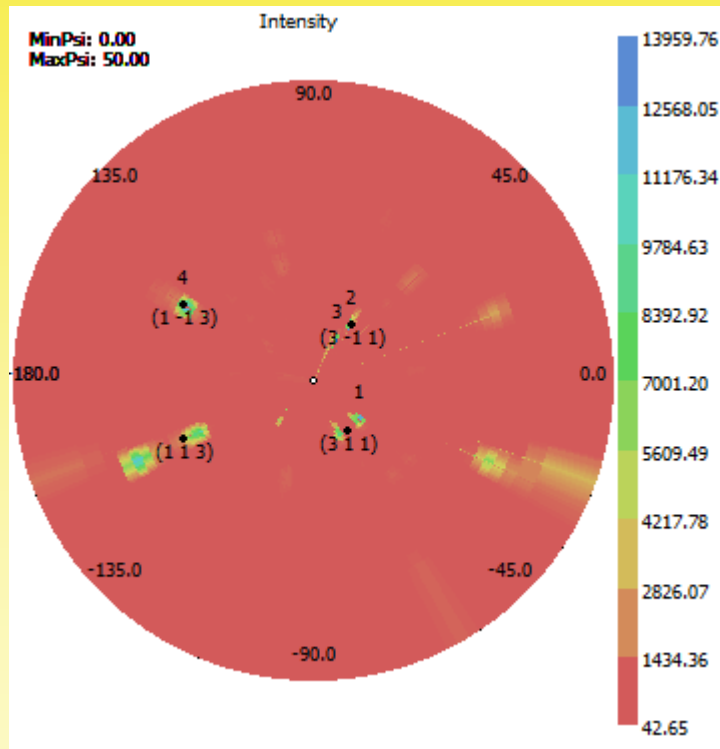
$\text{XEC} = 7.18 \cdot 10^{-6} \text{ MPa}^{-1}$

$\sigma = 1.7 \pm 6.7 \text{ Mpa}$

$\tau = 6.2 \pm 3.4 \text{ MPa}$

Stress Measurement Techniques 应力测量技术

Crystal Orientation (Pole figure technique) 晶体方向极图法

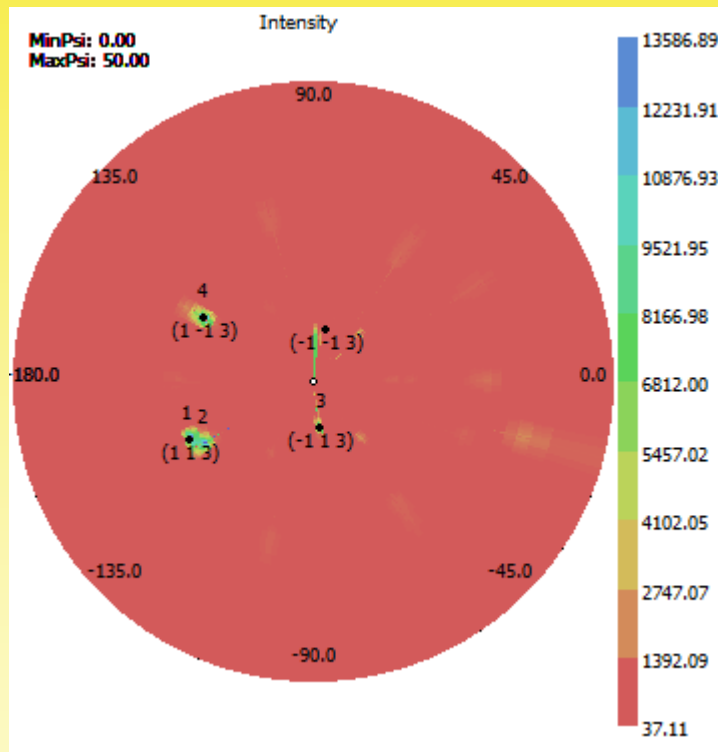


Sample 1: 样本一
X-Ray tube: *Mn*
Plane (hkl): *311*
Bragg angle, $2\theta = 155^\circ$

Pole figure collected on a Nickel Base Single crystal
镍基单晶中采集的的极图

Stress Measurement Techniques 应力测量技术

Crystal Orientation (Pole figure technique) 晶体方向极图法

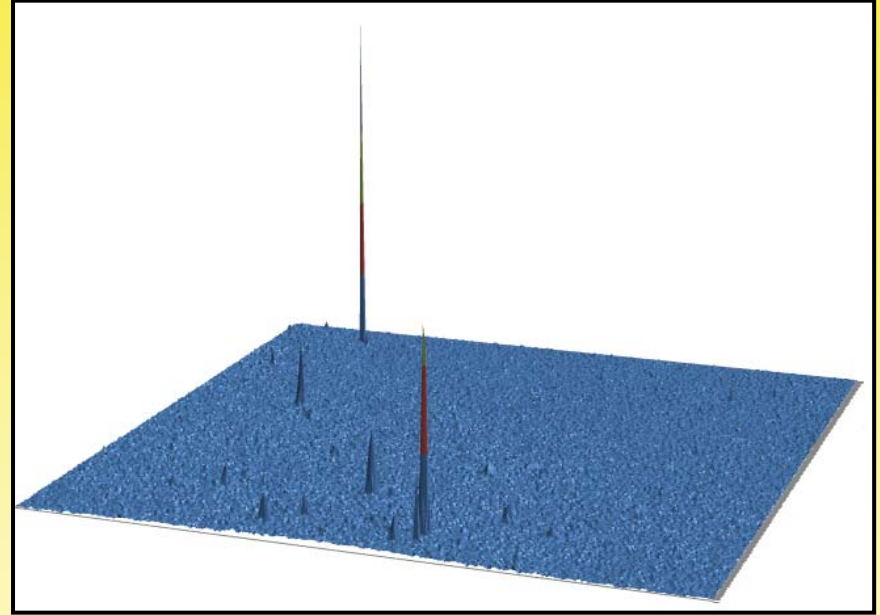


Sample 2: 样本二
X-Ray tube: *Mn*
Plane (hkl): 311
Bragg angle, $2\theta = 155^\circ$

Pole figure collected on a Nickel Base Single crystal
镍基单晶中采集的的极图

Stress Measurement Techniques 应力测量技术

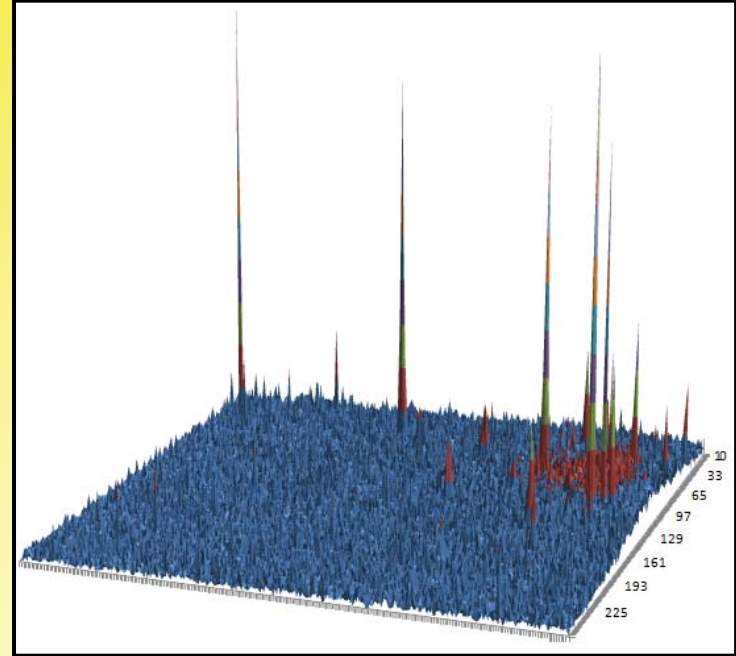
Crystal orientation (LAUE technique) 晶体方向（劳厄法）



- **Digital LAUE photograph and a 3D LAUE data, Sample 1**
劳厄数码照像与三维劳厄数据， 样本一

Stress Measurement Techniques 应力测量技术

Crystal orientation (LAUE technique) 晶体方向（劳厄法）



- **Digital LAUE photograph and a 3D LAUE data, Sample 2**
劳厄数码照像与三维劳厄数据， 样本二

Stress Measurement Techniques 应力测量技术

Crystal Orientation Pole figure versus LAUE techniques 晶体定向，极图法对劳厄法

- Single crystal orientation accuracy can be affected by the following: 影响单晶定向精度的因素
 1. Intensity of peaks 峰强度
 2. Poles overlap 极点重叠
 3. Mosaicity in the crystal 晶体中的马赛克
 4. Accuracy of poles position determination 极点定位精度
- Solution 解决方案
 1. Select low multiplicity peak for orientation 选择低阶 H K L 平面峰定向
 2. High resolution detector 高分辨探测器
 3. High power for high intensity peaks 大功率得到强峰

Stress Measurement Techniques 应力测量技术

Deployment 实施

- Use the single crystal orientation result to predict the position of the new poles, usually higher multiplicity
利用确定的单晶的方向预测新极点的位置，通常是较高阶的 H K L 平面
- Calculate the coordinates of the new poles (ψ, ϕ)
计算新极点的坐标(ψ, ϕ)
- Scan in space around the theoretical pole position to find the pole maximum position
在理论新极点位置附近扫描发现极点峰位

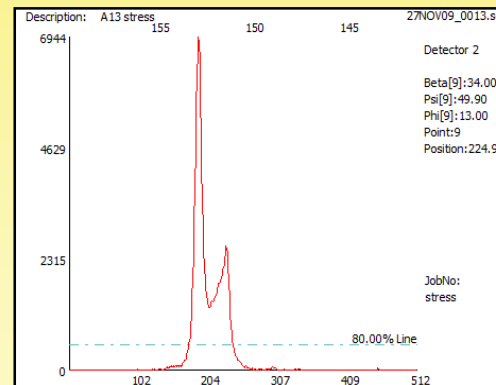
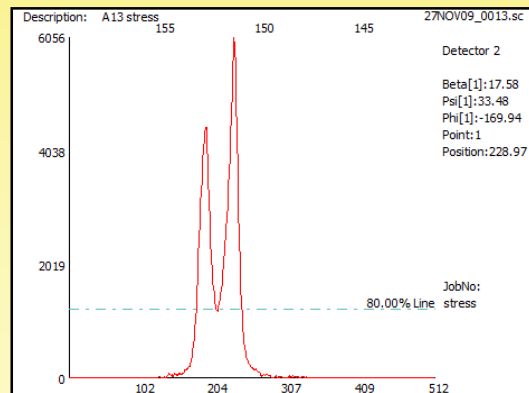
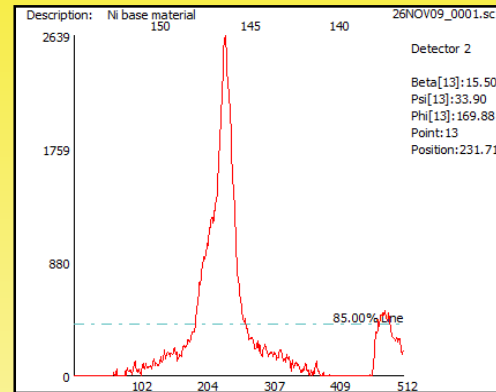
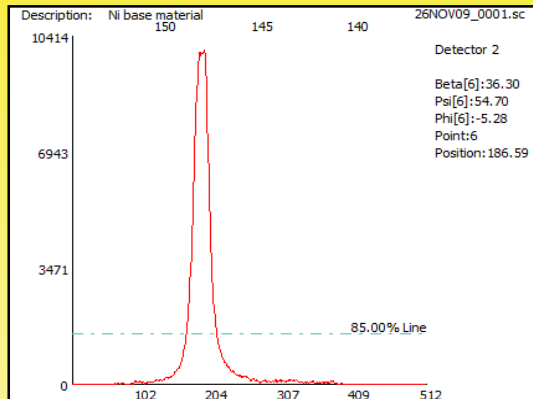
Stress Measurement Techniques 应力测量技术

Deployment 实施

- Collect a peak at the maximum position in (ψ, ϕ) and calculate the peak position in 2θ
在极点峰位处 (ψ, ϕ) 采集衍射峰, 计算峰位的 2θ
- Calculate strain
计算应变
- Using the elasticity theory, calculate the stress tensor.
应用弹性理论, 计算应力张量

Stress Measurement Techniques 应力测量技术

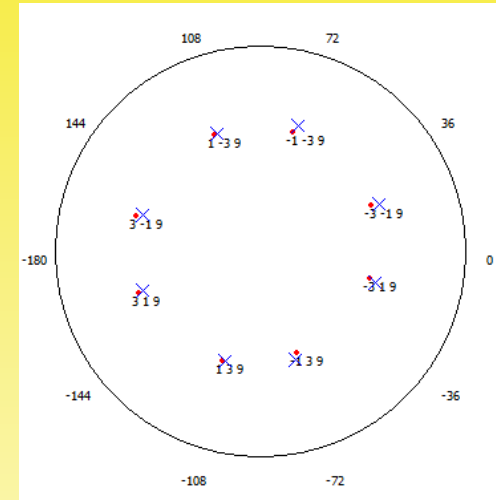
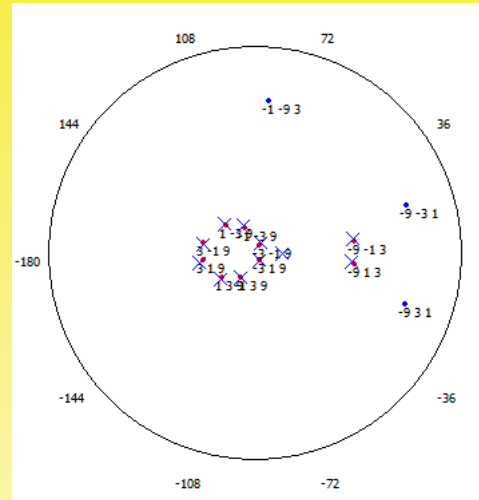
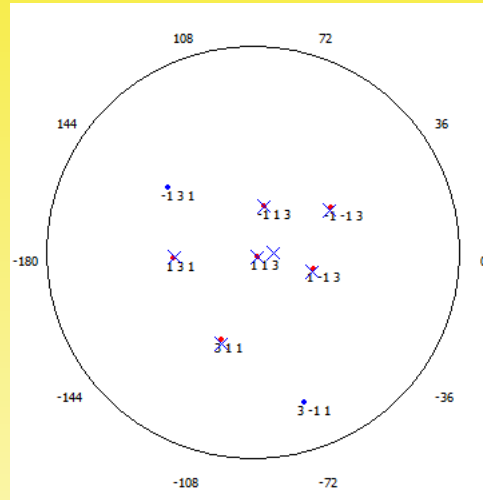
Results 结果



**Example of x-ray diffraction peaks collected on a single crystal
using Mo X-Ray tube**

实例：使用MO靶X光管采集的单晶X光衍射峰

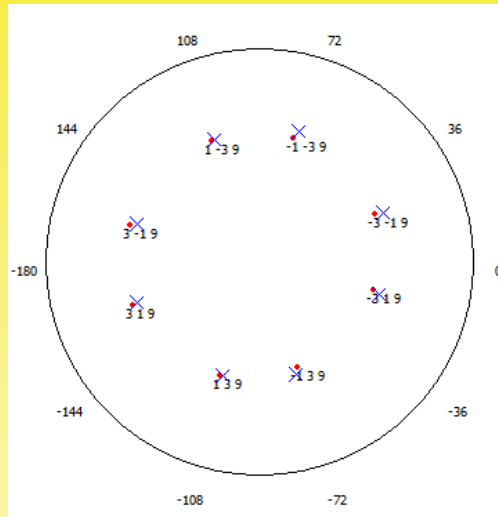
Stress Measurement Techniques应力测量技术



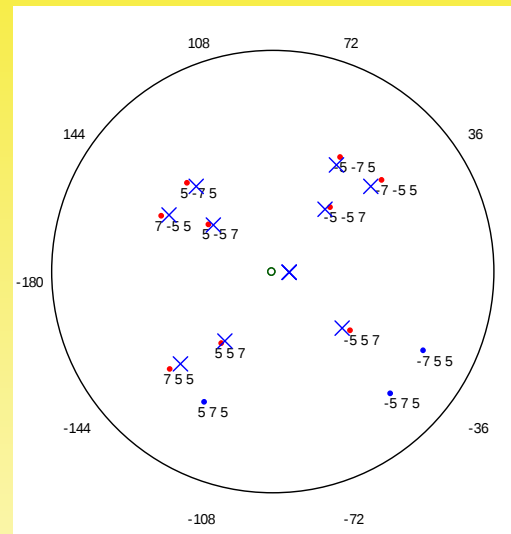
Example of poles layout collected on a single crystal

Stress Measurement Techniques 应力测量技术

Results 结果



Mo target



Mo target

Example of poles layout collected on a single crystal

实例：从单晶中采集的极点分布图

Stress Measurement Techniques 应力测量技术

Results 结果

Single Crystal					
JobNo:			Date: .		
PartNo:			Time:		
Description: Ni base material			Operator		
			Elapsed Time:		
Stress Tensor [MPa]			Error [MPa]		
-272.85	-73.90	81.16	0.00	0.00	0.00
	-219.31	97.11		0.00	0.00
		-0.00			0.00
Plane	Calculated Phi	Psi	Measured Phi	Psi	dspacing
(1 3 1)	-175.76	47.21	-176.26	46.71	1.082391
(3 1 1)	-109.50	52.39	-109.00	53.39	1.082026
(3 -1 1)	-71.13	67.50	0.00	13.60	N/A
(1 1 3)	-46.48	4.65	-47.48	5.15	1.085376
(1 -1 3)	-16.01	39.20	-17.51	39.20	1.084397
(-1 -1 3)	29.96	51.11	28.96	50.61	1.083755
(-1 1 3)	75.83	31.25	76.33	30.25	1.085336
(-1 3 1)	142.62	57.10	0.00	13.60	N/A

Example of Residual Stress results on a single crystal, shot peened subsurface

实例：单晶残余应力的计算结果

Summary

- Single crystal and Directionally Solidified materials can be characterized for both Crystal Orientation and Residual Stress
单晶和定向强化材料能够量化分析其晶体方向和残余应力
- Measurements were successfully applied in both lab and factory settings using Proto XRD equipment
应用Proto公司的X R D设备实验室设置和工厂设置成功地进行了有效的分析和测量
- Future development will include fast speed systems for LAUE and stress
未来的开发主要包括高速系统